L Number	Hits	Search T xt	DB	Time stamp
	3	(gate adj line).clm. and (gate n ar	USPAT;	2003/11/12
		(in ulating or di le tric)).clm. and (storage	US-PGPUB;	15:22
		n ar2 electr de).clm. and ((pr tective r	EPO; JPO;	
		protectant or protect or protecting) near	DERWENT;	
		layer).clm. and (contact or via or hole).clm.	IBM_TDB	
		and (capacitor near electrode).clm.		
-	12	(gate adj line).clm. and (gate near	USPAT;	2003/11/12
		(insulating or dielectric)).clm. and (storage	US-PGPUB;	15:23
1	0	near2 electrode).clm. and (contact or via or	EPO; JPO;	
		hole).clm. and (capacitor near	DERWENT;	
1		electrode).clm. and (method or	IBM_TDB	
		process).clm.	12	
	12	(gate adj line).clm. and (gate near	USPAT:	2003/11/12
		(insulating or dielectric)).clm. and (storage	US-PGPUB;	15:27
		near2 electrode).clm. and (contact or via or	EPO; JPO;	
		hole).clm. and (capacitor near	DERWENT;	
1		electrode).clm. and (method or	IBM_TDB	
			IBM_IDD	
		process).clm. and (storage near	1	
	8	capacitor).ti,ab,clm.	HERAT	2003/11/12
·	•	(gate adj line).clm. and (gate near	USPAT;	_
1		(insulating or dielectric)).clm. and (storage	US-PGPUB;	15:27
		near2 electrode).clm. and (contact or via or	EPO; JPO;	
1		hole).clm. and (capacitor near	DERWENT;	
		electrode).clm. and (method or	IBM_TDB	
İ		process).clm. and (storage near	1	
1	_	capacitor).ti,ab,clm. and (passivation).clm.		
	8	(gate adj line).clm. and (gate near	USPAT;	2003/11/12
		(insulating or dielectric)).clm. and (storage	US-PGPUB;	15:27
		near2 electrode).clm. and (contact or via or	EPO; JPO;	
		hole).clm. and (capacitor near	DERWENT;	
		electrode).clm. and (method or	IBM_TDB	
1		process).clm. and (storage near	-	
1		capacitor).ti,ab,clm. and (passivation).clm.		
		and pixel.clm.	1	
-	12	(gate adj line).clm. and (gate near	USPAT;	2003/11/12
		(insulating or dielectric)).clm. and (storage	US-PGPUB;	15:27
1		near2 electrode).clm. and (contact or via or	EPO; JPO;	
		hole).clm. and (capacitor near	DERWENT;	
,		electrode).clm. and (method or	IBM_TDB	
1	}	process).clm. and (storage near		
1	İ	capacitor).ti,ab,clm. and pixel.clm.	1	
.	10	(gate adj line).clm. and (gate near	USPAT;	2003/11/12
}	1	(insulating or dielectric)).clm. and (storage	US-PGPUB;	15:28
		near2 electrode).clm. and (contact or via or	EPO; JPO;	
	i	hole).clm. and (capacitor near	DERWENT;	
	-	electrode).clm. and (method or	IBM_TDB	
		process).clm. and (storage near		
	}	capacit r).ti,ab,clm. and pix l.clm. and		
1	ł	(gate adj insulating adj layer). Im.		

-	8	(gate adj lin).clm. and (gat n ar (insulating r diele tric)).clm. and (storage near2 electr de).clm. and (conta t or via r hol).clm. and (capacitor near	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/11/12 15:29
1		ele trode).clm. and (method or	IBM_TDB	
[process).clm. and (storage near		
		capacitor).ti,ab,clm. and pixel.clm. and		
		(gate adj insulating adj layer).clm. and		
İ		(contact adj hole).clm.		